EPFL - CMi

FLX 2320-S

WARNING

Only the **CMi Staff** is qualified to do a **service** or to do **maintenance**

User manual

1. Login

1.1. Logon on the ACCESS CONTROL SYSTEM on the zone computer to unlock the keyboard of the FLX 2320-S

2. Starting up

2.1. "SOURCE" light must be already ON (tool powered up) . Orange light .

2.2. "MAIN POWER" : Breaker ON ➜ . Green light .

2.3. "LASER" : Turn the key to ON ➜ . Green light .
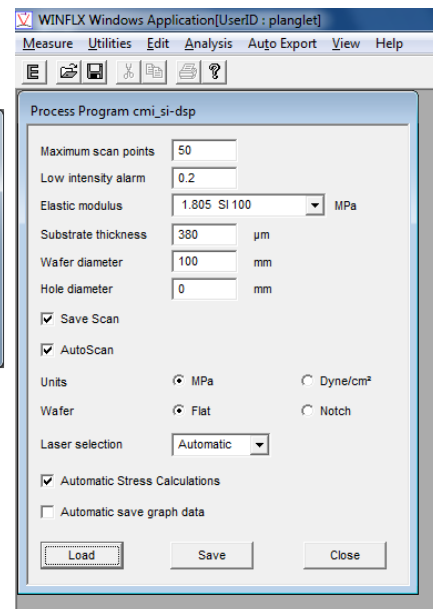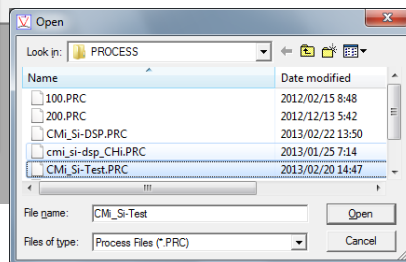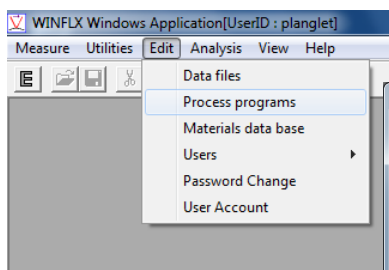
3. Loading

3.1. Open the door

3.2. **Place the Locator Ring for 4" wafer positioning at a given angle**

3.3. Put your substrate on the substrate holder

3.4. Close the door

4. Recipe Selection and Start Measurement

4.1. Start WINFLX, enter your login and password
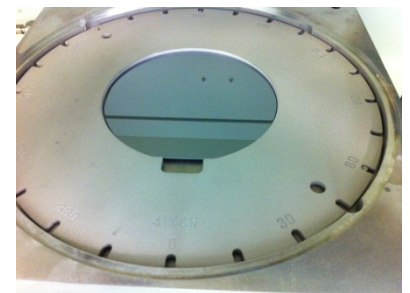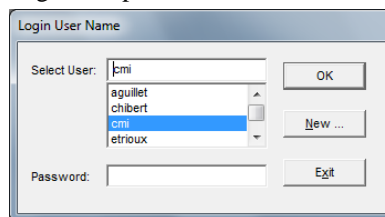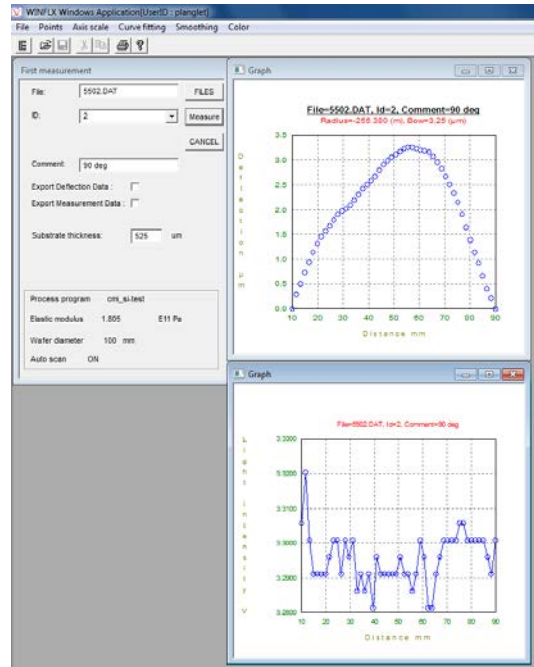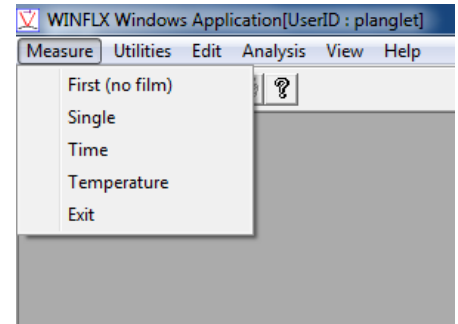
4.2. **Select the Process program (substrate)**

4.3. First measurement : no film **: Measure / First (no film)**
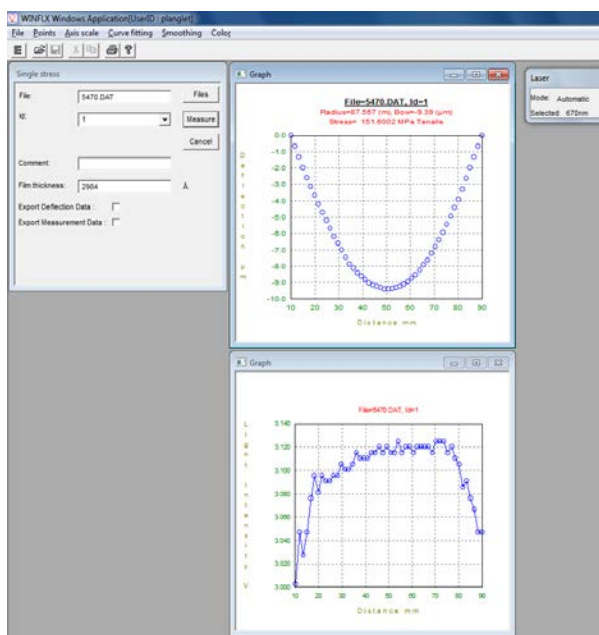
  - **Enter File name (for example ID number of the wafer)**

  - **Enter ID for the first measurement
    (for example: 1 @ 0° ; 2 @ 90°)**

  - **Thickness of the substrate can be adjusted if need be.**

4.4. Perform your thin film deposition on upper side of your wafer

4.5. Stress measurement

  4.5.1. Select "Single" from the Measure tab on the main screen

  - File : File name (for example ID number of the wafer)

  - ID of the first measurement (for example: 1 @ 0° ; 2 @ 90°)

  - Film thickness in Å

4.5.2. Press the "Measure" button. The instrument will perform a scan.

4.5.3. Results are then displayed: Intensity graph, Deflection graph with stress calculation.

5. Unloading

5.1. Open the door – Get back your substrate on the substrate holder – Close the door

6. Shutting down

6.1. **"LASER" : Turn the key to OFF**

6.2. **"MAIN POWER" : OFF**

6.3. **"SOURCE" light stays always ON (tool powered up) . Orange light .**

7. Logout

7.1. Logout from the FLX 2320-S
7.2. Logout from the ACCESS CONTROL SYSTEM.